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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Martin E. LEE

Group Art Unit: 2837

Application No.: 09/880,859

Examiner: B. Ro

Filed: June 15, 2001

Docket No.: 102305.00

For: GUIDELESS STAGE WITH ISOLATED REACTION FRAME

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TECHNOLOGY CENTER 2800

AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action dated December 28, 2001, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 34, 67, 72, 104, 112, 127, 133 and 142 as follows:

34. (Amended) A method of making a microlithography system that forms an image onto an object, comprising the steps of:

- providing an irradiation apparatus that irradiates the object with radiation to form the image on the object;
- providing a movable stage associated with the irradiation apparatus;
- providing a first support structure;
- providing a second support structure dynamically isolated from the first support structure;